

**IN THE SPECIFICATION:**

Please amend the Specification as follows:

**On page 11:**

[00043] *a first support structure (a mask table) MT: for supporting patterning devices (e.g. a mask) MA and connected to first positioning mechanism PM for accurately positioning the patterning devices with respect to item PL and measurement structure IF1;*

[00044] *a second object table (substrate table or substrate holder) WT: provided with a substrate holder for holding a substrate W (e.g. a resist-coated silicon wafer), and connected to second positioning mechanism PW for accurately positioning the substrate with respect to item PL and measurement structure ~~IF~~ IF2 (e.g., interferometric) to accurately indicate the position of the substrate and/or substrate table with respect to lens PL; and*